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Nanometer Scale Current-Voltage Characteristics of C₆₀ Films

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The current-voltage characteristics of C₆₀ films in nanometer scale are investigated by using atomic force microscope (AFM) with a conductive cantilever. The results can be explained by energy band theory assuming vacuum level alignment.

Keywords: C₆₀ films; AFM; current-voltage characteristics; interface

INTRODUCTION

Applications of molecular materials to optoelectronic devices are of practical significance [1-3]. With the discovery of fullerenes, a completely new family of molecules became available whose properties were expected to be very unusual due to the fact that they were made only of carbon and had cage-like structures [4, 5]. Studies have shown that solid C₆₀, in particular, has many interesting properties such as conductivity, superconductivity [6-7]. In addition, because of its high stability and relatively strong intermolecular interactions, C₆₀ is suitable for thin film preparation.

The motivation to fabricate integrated circuits of ever increasing density will require the measurement of electrical properties with both lateral and vertical resolution approaching 10 nm or better. The electrical current I flowing as a function of tip displacement s towards an individual C₆₀ molecule is investigated by scanning tunneling microscopy (STM) [8]. The investigation on the metal-vacuum-semiconductor junction structure by STM has shown that variations in tunneling characteristics on an atomic scale can be detected. There is no report of the nanometer scale electrical properties of ultra-thin C₆₀ films by AFM. In this paper, we describe studies of the electrical characteristics of C₆₀ films on different substrate (MoS₂, HOPG, Au(111)) by AFM with a conductive cantilever. The information obtained by AFM is related to the C₆₀ films and the interface between the C₆₀ films and the substrate with near atomic or nanometer resolution.

EXPERIMENTAL DETAILS

The commercially available C_{60} powder was degassed at 200°C in high level vacuum (10^{-6} Pa) for 10 hours before use. The C_{60} powder was introduced into a molecular beam epitaxy (MBE) apparatus with a base pressure of about 1×10^{-7} Pa. The thickness of films was monitored with a quartz crystal oscillator. The thickness of C_{60} thin films ranges from a monolayer to 5 layers generally grown at a rate of 0.2 nm/min. The MoS_2 , HOPG substrates were cleaved in air and immediately transferred into the vacuum chamber. The epitaxial film of Au(111) was prepared on mica and transferred into the MBE system without exposed to the air.

The topography observation and current-voltage measurement of the C_{60} thin films were carried out by using a SPM unit SPI-3700 (Seiko Elect. Ind. Co.) at ambient environment. For the topography observation, contact mode AFM was employed with a commercial gold-coated cantilever (The resonance frequency was 14 kHz and spring constant was 0.22 N/m). The current-voltage characteristics were obtained by applying DC voltage to the sample surface through the conductive cantilever. The sample was connected electrically to a metal sample stage by conductive paste. All the images shown in this paper are original data only with tilting treatment.

RESULTS AND DISCUSSION

Figure 1(a) shows the contact mode AFM image of C_{60} grains deposited on a Au(111) substrate. Au(111) substrate makes up of about $1 \mu m$ large islands and about 200 nm small islands. Although C_{60} forms island on Au(111) too, they can be distinguished from Au(111) substrate by the grains size. The average size of C_{60} islands was in the range of 50-100 nm. Current-voltage characteristics can be measured at different locations in the image, as indicated in figure 1(b). Curve 4 and 5 show the conductivity of the Au(111) substrate at different location. The difference between the two curves is due to the interface between the large island (curve 5) and the small island (curve 4). The current-voltage curves of C_{60} grains (curve 1, 2 and 3) show Schottky behavior which indicates the formation of Schottky contact between substrate Au(111) and C_{60} grains.

Figure 2(a) indicates the AFM image of C_{60} multilayers on HOPG substrate. It can be found that the isolated grains have been formed on the substrates, most of these grains are monolayer, however, the second layer appears in some regions. The current-voltage characteristics can be measured at different locations in the image, as indicated in figure 2(b). The current-voltage curve of the bare substrate (curve 1) shows Ohmic behavior. The current-voltage curves obtained at the C_{60} grains (curve 2, 3) show a linear voltage dependence characteristic of Ohmic behavior at low applied voltages ($|V| \leq 0.4$ V). For larger voltage, the exponential dependence dominates the I-V characteristic. The currents at C_{60} grains are lower than that of bare HOPG substrate at the same applied voltages.

Figure 3(a) shows the AFM image of C_{60} multilayers on MoS_2 substrate. It can be found that isolated grains have been formed on the substrates, most of these grains are the first layer, however, the second, third layer appears in some regions. Current-voltage characteristics can be measured at different locations in the image, as indicated in figure 3(b). The current-voltage curve of bare substrate (curve 1) shows rectification behavior. The current-voltage curves obtained at the C_{60} monolayer and multilayers (curve 2, 3) show the formation of a barrier of semiconductor-semiconductor contact between substrate MoS_2 and C_{60} grains. The currents at C_{60} grains are lower than that of bare MoS_2 substrate at the same applied voltages. For the current through the first layer (curve 1) and the multilayers (curve 3), lower currents are obtained through the multilayers. The decrease of the current value due to the increase of the thickness of the C_{60} thin films results from the resistance of C_{60} thin films as an n-type semiconductor.

From the viewpoint of energy band, the center of the HOMO-LUMO gap of C_{60} is 4.8 eV [9], the Fermi level for Au(111) is 5.31 eV, the Fermi level for HOPG is 4.5 eV and the Fermi level for MoS_2 is 5.2 eV [10]. When C_{60} films deposited on Au(111), HOPG and MoS_2 substrate respectively, a Schottky barrier will form between C_{60} films and Au(111) substrate, no barrier will form between C_{60} and HOPG substrate and a barrier will form between C_{60} and MoS_2 substrate assuming vacuum level alignment.

CONCLUSIONS

From the results and discussion in the previous paragraph, the nanometer scale electrical characteristics of C_{60} films and the interface between C_{60} films and substrate can be obtained by AFM. The current-voltage measurements on the monolayer or multilayer C_{60} thin films indicate that its operation characteristics can be qualitatively described by the conventional energy band theory assuming vacuum level alignment.

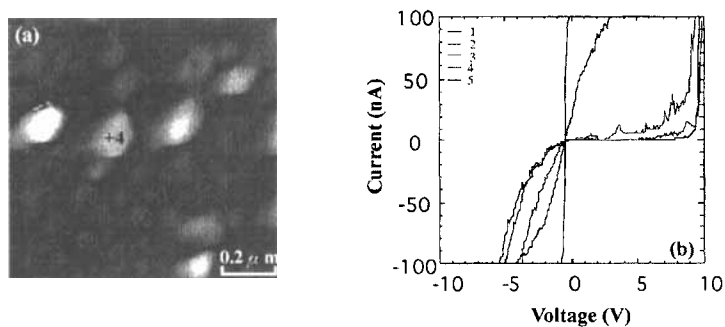


Fig. 1 Topography (a) and I-V curves (b) of C_{60} growth on Au(111)

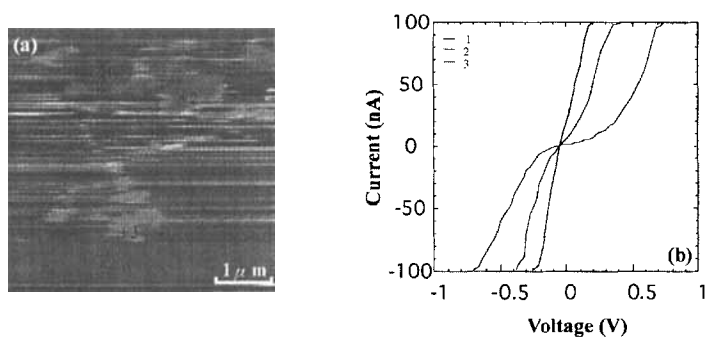


Fig. 2 Topography (a) and I-V curves (b) of C_{60} growth on HOPG

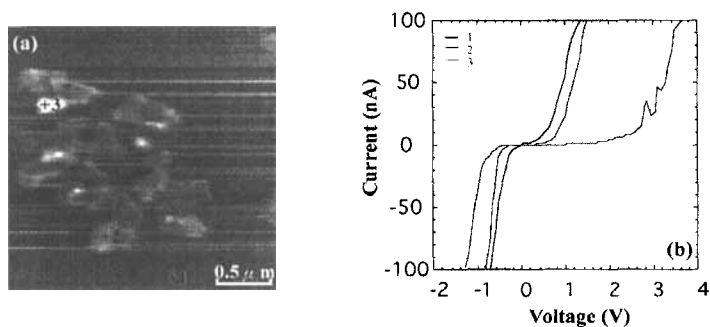


Fig. 3 Topography (a) and I-V curves (b) of C_{60} growth on MoS_2

See color plate XVIII at the back of this issue.

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